

LAMINATE AND METHOD FOR PRODUCING SAME**ABSTRACT**

The object of the present invention is to provide a metallic material which can be employed as a constituent member of a semiconductor production device and has excellent corrosion resistance, particularly excellent corrosion resistance to acids. A laminate according to the present invention comprises a metallic base material, a first nickel-containing plating film layer formed on the metallic base material, a gold plating film layer formed on the first nickel-containing plating film layer, a second nickel-containing plating film layer formed on the gold plating film layer, and a nickel fluoride film layer formed on the second nickel-containing plating film layer.

[Fig. 1]